

# ALD unique single hot wall Fiji 200 reactor COMEF Aparatura Naukowo-Badawcza

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COMEF company represents the world leading research and measurement equipment producers for the different kind of science and industry, especially for nanotechnology.

The company has a stable team of staff members whose qualifications are systematically raised through training and courses. COMEF's employees actively participate in professional national and international conferences.

We offer full range of facilities and the service training.

We are proud to introduce a new Hitachi line of instruments for semiconductor R&D with improved CFE gun technologies.

**SU-9000** system is an ultra-high resolution Scanning Electron Microscope with following features:

- Superior low-kV performance for observation of beam sensitive materials.
- Next generation Hitachi In-lens SEM optics allows for routine observation at 1 million times.
- Newly designed CFE GUN provides high brightness and extremely stable emission current.
- Highly engineered instrument enclosure featuring both superior strength and stability to allow for high resolution imaging in a broad range of environmental conditions
- Newly designed objective lens provides for high resolution imaging at low acceleration voltage.
- Side entry sample exchange system increases throughput by reducing the time required to change samples and by automatically positioning the sample at the correct WD

On 3rd "Jaszowiec" 2014 International School & Conference on the Physics of Semiconductors we are happy to introduce you:  
„Unique single hot wall Fiji 200 ALD reactor”



Fig.1 Fiji™ G2 reactor

During the seminar we will present our company portfolio and introduce you the second generation of Fiji 200 ALD reactor with benefits and differences in single wall ALD reactor designs:

- Flow-optimized ALD chamber for thermal or plasma deposition.
- Top mounted precursor and gas delivery
- Integrated ALD Shield™ vapor trap (keeps pumping line components cleaner)
- Process Modes: Thermal Continuous Mode for high speed depositions, Thermal Expo Mode with stop valve operation for ultra-high aspect ratio structures (> 200:1), and Plasma Mode.

Hot wall design allows to:

- Faster thermal response for temperature steps and pre-heating. Greater thermal flexibility for R&D processing.
- Exposure Mode Capable for HAR samples - single pressure system with one chamber.
- In situ metrology ports are available in the process space, Ellipsometer, QCM, OES.